

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re application of: Gurtej S. Sandhu and Sujit Sharan

Serial No.:

Filed: November 12, 1999

For: METHOD FOR IN-SITU CLEANING OF
INDUCTIVELY-COUPLED PLASMA CHAMBERS

§
§ Group Art Unit:
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§ Examiner:
§
§ Atty. Docket: 95-0392.02
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§

INFORMATION DISCLOSURE STATEMENT

Assistant Commissioner for Patents
Washington, D.C. 20231

Dear Sir:



In compliance with the duty of disclosure under 37 C.F.R. § 1.56, Applicants respectfully request that this Information Disclosure Statement be entered and that the references listed on the attached Form PTO-1449 be considered by the Examiner and made of record. Copies of the listed references are enclosed for the convenience of the Examiner.

In accordance with 37 C.F.R. § 1.97(b), this Information Disclosure Statement is not to be construed as a representation that a search has been made or that no other possible material information as defined in 37 C.F.R. § 1.56(a) exists.

The following references are submitted for the Examiner's review:

U.S. Patents

<u>U.S. Patent No.</u>	<u>Issue Date</u>	<u>Inventor</u>
5,824,607	10/20/98	Trow et al.
5,817,534	10/06/98	Ye et al.
5,812,403	09/22/98	Fong et al.

5,792,272	08/11/98	van Os et al.
5,788,799	08/04/98	Steger et al.
5,788,778	08/04/98	Shang et al.
5,614,055	03/25/97	Fairbairn et al.
5,514,246	05/07/96	Blalock
5,409,563	04/25/95	Cathey
5,393,709	02/28/95	Lur et al.
5,389,496	02/14/95	Calvert et al.
5,389,195	02/14/95	Ouderkirk et al.
5,384,289	01/24/95	Westmoreland
5,368,687	11/29/94	Sandhu et al.
5,252,518	10/12/93	Sandhu et al.
5,240,739	08/31/93	Doan et al.
4,878,994	11/07/89	Jucha et al.
4,820,377	04/11/89	Davis et al.
4,795,880	01/03/89	Hayes et al.

Other References:

"Advanced Plasma Sources: What's Working?," *Semiconductor International*, pp. 56-58, 60, May 1994.

Applicants understand that no fee or certification is required for the submission and consideration of this information at this time.

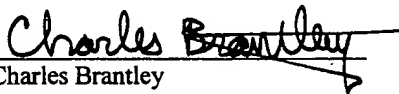
If there are any matters which may be resolved or clarified through telephone interview, the Examiner is respectfully requested to contact Applicants' undersigned attorney at the number indicated.

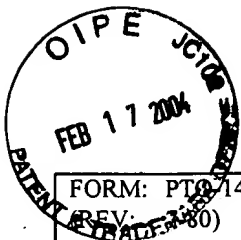
* * * *

A Form PTO-1449 is enclosed herewith.

Respectfully submitted,

Date: 11/12/99


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FORM: PTO 1449
(REV. 3-80)U.S. DEPARTMENT OF COMMERCE
PATENT AND TRADEMARK OFFICEAtty Docket No:
95-0392.02

Serial No:

INFORMATION DISCLOSURE STATEMENT BY APPLICANT

Applicant:
Sandhu, et al.Filing Date:
November 12, 1999

Group:

(37-CFR 1.98(b))

(use several sheets if necessary)

U.S. PATENT DOCUMENTS

Examiner Initial	Document Number	Date	Name	Class	Subclass	
	AA	5,824,607	10/20/98	Trow et al.	438	732
	AB	5,817,534	10/06/98	Ye et al.	438	10
	AC	5,812,403	09/22/98	Fong et al.	364	468.28
	AD	5,792,272	08/11/98	van Os et al.	118	723 IR
	AE	5,788,799	08/04/98	Steger et al.	156	345
	AF	5,788,778	08/04/98	Shang et al.	134	001
	AG	5,614,055	03/25/97	Fairbairn et al.	156	345
	AH	5,514,246	05/07/96	Blalock	156	643.1
	AI	5,409,563	04/25/95	Cathey	156	643
	AJ	5,393,709	02/28/95	Lur et al.	437	228
	AK	5,389,496	02/14/95	Calvert et al.	430	315
	AL	5,389,195	02/14/95	Ouderkirk et al.	156	643
	AM	5,384,289	01/24/95	Westmoreland	437	245
	AN	5,368,687	11/29/94	Sandhu et al.	156	664
	AO	5,252,518	10/12/93	Sandhu et al.	437	200
	AP	5,240,739	08/31/93	Doan et al.	427	126.1
	AQ	4,878,994	11/07/89	Jucha et al.	156	643
	AR	4,820,377	04/11/89	Davis et al.	156	643
	AS	4,795,880	01/03/89	Hayes et al.	219	121.52

FOREIGN PATENT DOCUMENTS

Examiner Initial	Document Number	Date	Country	Class	Subclass	Translation Yes	No
	AT					<input type="checkbox"/>	<input type="checkbox"/>
	AU					<input type="checkbox"/>	<input type="checkbox"/>

Initial

OTHER ART (including author, title, date, pertinent pages, etc.)

	AV		"Advanced Plasma Sources: What's Working?", <i>Semiconductor International</i> , pp. 56-58, 60, May 1984
	AW		
	AX		

Examiner:

Date Considered:

EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication with applicant.